	Hits	Search Text	DBs
35	2	((object or substrate or wafer) same (resin or photoresist or resist) same cur\$4) and ((stor\$4 near9 (device or container or holder) or bath) same (liquid or solvent or ether or (TPM near6 ether)) same (strip\$4 or remov\$4 or eliminat\$4 or dissolv\$4) same (resin\$4 or photoresist or resist or polymer) same (overflow\$4 or submers\$4 or immers\$4)) and ((alter\$4 or chang\$4 or adjust\$4) same (conductivit\$4 or electric\$4 or resistance or resistivity or impedance or voltage) same (solution or solvent) same (LED or (light near3 emit\$4 near4 diode) or respons\$4 or signal))	USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
36	40	((object or substrate or wafer) same (resin or photoresist or resist) same (cur\$4 or pattern)) and (((stor\$4 near9 (device or container or holder)) or bath) same (liquid or solvent or ether or (TPM near6 ether)) same (strip\$4 or remov\$4 or eliminat\$4 or dissolv\$4) same (resin\$4 or photoresist or resist or polymer)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
37	73	polymer\$3)) and ((resist or resin or photoresist) same (fluid or solution or liquid or solvent or strip\$4) same (conductivit\$4 or electric\$4 or conduct\$4 or	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB